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## **ALD NANOSOLUTIONS, Inc. Opens Facility**

**February 10, 2005** – P. Michael Masterson, CEO and Chairman of ALD NanoSolutions, Inc., of Broomfield, Colorado, announced today that ALD NanoSolutions, Inc., has opened a development and research facility in Broomfield. The company's Particle ALD™, recently named by Editors of R&D Magazine as one of the 100 most technologically significant products introduced into the world marketplace in 2004, will be refined at the plant located on 580 E. Burbank Street.

According to Karen Buechler, President and Chief Technology Officer of ALD NanoSolutions, two systems in the plant will be ready to provide samples for commercialization by April 2005. The systems will include one fluidized bed reactor, which will hold the capability to provide kilogram batches of Atomic Layer Deposition (ALD) to address grant awards and corporate customer requests. Analysis on results of the research being performed for the Department of Energy, the National Science Foundation, the Department of Defense and others will contribute to future research made possible with the new facility's capabilities.

ALD NanoSolutions, Inc. was founded in 2001 by P. Michael Masterson, Dr. Karen Buechler, and University of Colorado (CU) Professors Dr. Steven George and Dr. Alan Weimer. The company's proprietary technology is based on Atomic Layer Deposition (ALD) coating chemistry processing methods for particulate and polymeric surfaces developed at CU. The company is focused on commercializing its nano-coating processes, called Particle ALD™ and Polymer ALD™, and is targeting collaborative research agreements with domain partners for the discovery and validation of innovative composite materials in selected industries.

“The gate to the future applications is through the ability to innovate at the surface level where particles interact with the surrounding environment. Particle-ALD™ serves as an enabling technology, potentially providing for the control of ultrafine particle chemical, electrical, optical, magnetic, physical, and other surface properties. We are looking at compelling ALD applications with commercialization potential that can be realized during the next three to five years, said Masterson.”

The University of Colorado has licensed intellectual property to ALD NanoSolutions, Inc. and work performed under government Small Business Technology Transfer (STTR) awards from NSF, DOE, and DoD helped validate the technology in CU labs. For further information, please visit [www.aldnanosolutions.com](http://www.aldnanosolutions.com).